

WHAT IS CLAIMED IS:

1. An optical interference display, at least comprising:
 - a conductive transparent layer; and
 - a dielectric layer located on the conductive transparent layer, wherein a incident light irradiate form a side of the conductive transparent layer, the material of the conductive transparent layer and a thickness of the conductive transparent layer absorb at least 30 % of the incident light.
2. The optical interference display of claim 1, wherein a material of the conductive transparent layer is selected from the group consisting of ITO, IZO, ZO, IO and the combination thereof.
3. The optical interference display of claim 1, wherein a material of the dielectric layer comprises silicon oxide, silicon nitride or metal oxide.
4. The optical interference display of claim 1, wherein lattice of the conductive transparent layer is disordered.
5. The optical interference display of claim 1, wherein axes of every part of the conductive transparent layer are different.
6. The optical interference display of claim 1, wherein the conductive transparent layer further comprises more than 100ppm impurity.

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7. An optical interference display plate, at least comprising:
two conductive transparent layers; and
two dielectric layers, each of the dielectric layers located on each of the
conductive transparent layers, wherein a incident light irradiate form a side of the
5 conductive transparent layer, the material of the conductive transparent layer and a
thickness of the conductive transparent layer absorb at least 30 % of the incident light.

8. The optical interference display of claim 7, wherein a material of the
conductive transparent layer is selected from the group consisting of ITO, IZO, ZO, IO
10 and the combination thereof.

9. The optical interference display of claim 7, wherein a material of the dielectric
layer comprises silicon oxide, silicon nitride or metal oxide.

15 10. The optical interference display of claim 7, wherein lattice of the conductive
transparent layer is disordered.

11. The optical interference display of claim 7, wherein axes of every part of the
conductive transparent layer are different.

20 12. The structure of claim 7, wherein the conductive transparent layer further
comprises more than 100ppm impurity.

13. An optical interference display plate, at least comprising:

a first conductive transparent layer;

a first dielectric layer located on the first conductive transparent layer;

a second conductive transparent layer located on the first dielectric layer;

a second dielectric layer located on the second conductive transparent layer;

5 a third conductive transparent layer located on the second dielectric layer; and

a third dielectric layer located on the third conductive transparent layer,

wherein a incident light irradiate form a side of the first conductive transparent layer, the material of the first conductive transparent layer, the second conductive transparent layer, the third conductive transparent layer and a thickness of the first

10 conductive transparent layer, the second conductive transparent layer, the third conductive transparent layer absorb at least 30 % of the incident light.

14. The optical interference display of claim 13, wherein a material of the first conductive transparent layer, the second conductive transparent layer and the third

15 conductive transparent layer is selected from the group consisting of ITO, IZO, ZO, IO and the combination thereof.

15. The optical interference display of claim 13, wherein a material of the first dielectric layer, the second dielectric layer and the third dielectric layer comprises

20 silicon oxide, silicon nitride or metal oxide.

16. The optical interference display of claim 13, wherein the lattice of the first conductive transparent layer and the second conductive transparent layer is different.

17. The optical interference display of claim 13, wherein the lattice of the second conductive transparent layer and the third conductive transparent layer is different.

18. The optical interference display of claim 13, wherein axis of the first 5 conductive transparent layer and the second conductive transparent layer is different is different.

19. The optical interference display of claim 13, wherein axis of the second conductive transparent layer and the third conductive transparent layer is different is 10 different.

20. The structure of claim 13, wherein the conductive transparent layers further comprises more than 100ppm impurity.